

# Gallium Arsenide

## Epitaxy Ready Polished Wafers



Wafer Technology offers single crystal Gallium Arsenide grown at low pressure from high purity polycrystalline Gallium Arsenide in a vertical temperature gradient (VGF-Vertical Gradient Freeze).

### MECHANICAL SPECIFICATIONS

Gallium Arsenide can be supplied in as-cut, etched or polished wafer forms. All slices are individually laser scribed with ingot and slice identity to ensure perfect traceability.

### ORIENTATION SPECIFICATIONS

Surface orientations are offered to an accuracy of +/- 0.05 degrees using a triple axis X-Ray diffractometer system. Substrates can also be supplied with very precise misorientations in any direction from the growth plane. Higher index substrates of the type (n,1,1) where n = 1,2,3,4,5,6 etc and orientations such as (110) are also available. We also offer wafers with cut and/or cleaved flats.

### SURFACE SPECIFICATIONS

All wafers are offered with high quality epitaxy-ready finishing. Surfaces are characterised by in-house, advanced optical metrology techniques which include Surfscan haze and particle monitoring, spectroscopic ellipsometry and grazing-incidence interferometry.

### PACKAGING

#### Polished Wafers

Coin-style wafer shipper, individually sealed in two outer bags in inert atmosphere. Cassette shipments are available on request.

#### As-cut Wafers

Cassette shipment. (Glassine bag available on request).

#### 'Process Trial' wafers

Coin-style wafer shipper, individually sealed in one outer bag.

If you do not see the specification you require, please call for details on +44 (0)1908 210444 or email [sales@wafertech.co.uk](mailto:sales@wafertech.co.uk)

Wafer Specifications		
Diameter Slices	2"	3"
Orientation	(100) ± 0.1°	(100) ± 0.1°
Diameter (mm)	50.5 ± 0.5	76.2 ± 0.4
Flat Option	EJ	EJ
Flat Tolerance	± 0.5°	± 0.5°
Major Flat Length (mm)	16 ± 2	22 ± 2
Minor Flat Length (mm)	8 ± 1	11 ± 1
Thickness (µm)	350 ± 25 or 500 ± 25	625 ± 25

Electrical and Doping Specifications					
Dopant	Type	Resistivity Ω cm	Carrier Concentration cm <sup>3</sup>	Mobility cm <sup>2</sup> V <sup>-1</sup> s <sup>-1</sup>	E.P.D. cm <sup>-2</sup>
Undoped	Semi-Insulating	≥10 <sup>7</sup>	Not specified	≥5000	2" ≤2000 3" ≤5000
Zinc	p-type	Not specified	5 x 10 <sup>18</sup> - 5 x 10 <sup>19</sup>	Not specified	2" ≤3000 3" ≤5000
Mid Silicon	n-type	Not specified	(1-10) x 10 <sup>17</sup>	≥2000	2" ≤1500
High Silicon	n-type	Not specified	(1-5) x 10 <sup>18</sup>	Not specified	2"&3" Grade 1 ≤100 Grade 2 ≤500

Tighter electrical ranges are available on request.

Flatness Specifications			
Wafer Form	2"	3"	
Polish/Etched	TTV (µm)	<10	<10
	Bow (µm)	<10	<10
	Warp (µm)	<10	<10
Polish/Polish	TTV (µm)	<3	<5
	Bow (µm)	<3	<5
	Warp (µm)	<10	<10



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